Special Issue

Aluminum Nitride – From Crystal Growth to Device Development

Message from the Guest Editors

Aluminum nitride (AlN) is an ideal material for a wide range of high-power and high-frequency applications (e.g., UV emitters and UV sensors in the wavelength range well below 200 nm, and for piezoelectric and temperature sensing at high temperatures) due to its outstanding electronic, mechanical and chemical properties (resistivity 107–1013 Wcm, band gap 6.2 eV, thermal conductivity 340 Wm-1K-1, thermal decomposition > 2400 °C, Mohs hardness 9). To date, most applications of AlN have been based on the deposition of layers of nitride semiconductors by metal-organic chemical vapor deposition (MOCVD) on foreign substrates such as sapphire. The use of AlN native substrates would bring dramatically better performance of the corresponding devices because of the reduction in defect density by orders of magnitude. The only known method to fabricate industrially relevant AlN single crystals is the PVT (sublimation/reconstruction) method at temperatures greater than 2000 °C. The associated problems, such as nucleation on native substrates, grain expansion, wafering or n-doping, are still the subject of intensive investigations.

Guest Editors

Dr. Jürgen Wollweber

Former Head AlN at the Institute for Crystal Growth Berlin, 12489 Berlin, Germany

Prof. Dr. Liang Wu

Ultratrend Technologies Co., Ltd., Hangzhou 311199, China

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Applied Sciences
Editorial Office
MDPI, Grosspeteranlage 5
4052 Basel, Switzerland
Tel: +41 61 683 77 34
applsci@mdpi.com

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Editor-in-Chief

Prof. Dr. Giulio Nicola Cerullo
Dipartimento di Fisica, Politecnico di Milano, Piazza L. da Vinci 32, 20133 Milano, Italy

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